

# NuSolv KDS Alkaline NMP Based Photoresist Stripper

**PRODUCT DESCRIPTION:** NuSolv KDS photoresist stripper and ash/etch residue remover provides versatile cleaning in traditional semiconductor applications; compound semiconductor and packaging applications (flip chips/bumps). NuSolv KDS is Semicon grade and meets electronics grade specs.

### CHARACTERISTICS:

- Added alkalinity boots photoresist removal in 5–20 minutes
- 100% water soluble formulation—no intermediate solvent rinse required resulting in decreased total process time and costs
- Designed to provide broad process latitude in terms of processing time and temperature
- Long bath life—typically greater than 24 hours
- Does not contains fluoride or hydroxylamine

### DIRECTIONS FOR USE:

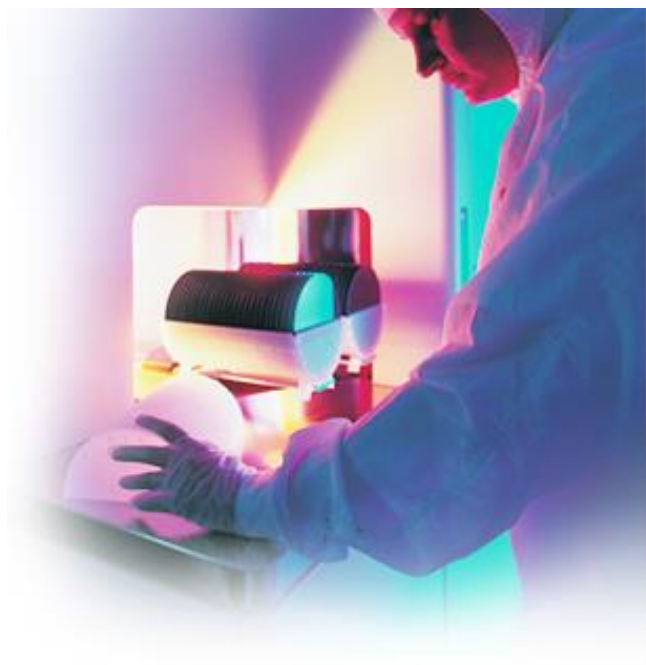
1. Bath or Batch Spray      65° to 85° C      5-20 min
2. DI Rinse
3. Dry

### COMPATIBLE MATERIALS:

- Stainless Steel
- Ni/Phos
- Silicon
- Quartz
- PTFE
- Polypropylene
- PFA

### PHYSICAL PROPERTIES:

	NuSolv KDS
Flash Point – open cup	103°C
Flash Point – closed cup	93°C
pH, @ 5% bv	12.0
Bath Life	>24 hours
Freezing Pont	-30°C
Boiling Point	165°C
Solubility in water	Complete
Viscosity (@22°C)	<10 cps
Surface Tension	41 dyne/cm
Specific Gravity	0.913 kg/L



**Availability:** 5-gallon and 55-gallon containers; 300 gallon tote-bins and bulk tankers.

**Shipment:** Freight classification is “cleaning compound, NOBIN – Liquid.”

**Storage:** Keep out of direct sunlight. Keep from freezing. Store between 40-120°F.

**Disposal:** Dispose of in accordance with local, state, and federal regulations. For assistance with disposal contact NuGeneration Technologies at 888-99-NuGen or email: [salesteam@nugentec.com](mailto:salesteam@nugentec.com).